

FORM PTO-1449 (Modified)			ATTY. DOCKET NO. SwRI-2890-04	APPLICATION NUMBER 10/693,076			
LIST OF INFORMATION PROVIDED BY APPLICANT (Use several sheets if necessary)			APPLICANT Ronghua WEI, et. al.				
			JUL 24 2007	FILING DATE October 24, 2003	GROUP ART UNIT 1775		
REFERENCE DESIGNATION:			U.S. PATENT DOCUMENTS				
Examiner Initial		Document No.	Date	Patentee	Class	Subclass	Filing Date if Appropriate
ML	AA	3,952,334	04-27-1976	Bokros			
ML	AB	2004/0115377 A1	12-11-2003	Wei			
ML	AC	7,052,736	05-30-2006	Wei			
ML	AD	6,767,436 B2	07-2004	Wei			
ML	AE	6,193,852 B1	02-2001	Yumshtyk			
ML	AF	5,026,466 A	06-1991	Wesemeyer			
ML	AG	2006/0076231 A1	04-13-2006	Wei			
ML	AH	4,221,652	09-09-1980	Kuriyama			
ML	AI	5,272,735	12-21-1993	Bryan			
ML	AJ	4,009,090	02-22-1977	Veigel			
ML	AK	4,169,477	10-02-1979	Bokros			
ML	AL	4,444,643	04-1984	Garrett			
ML	AM	4,179,351	12-1979	Hawton			
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ML	AO	2006/0076235 A1	04-13-2006	Wei			
REFERENCE DESIGNATION:			FOREIGN PATENT DOCUMENTS				
Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation Yes No
ML	AP	UK 2-125-441 A	07-07-1983	United Kingdom			
OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)							
ML	AQ	USPTO, First Office Action for Application Number 10/167,189, July 16, 2003.					
ML	AR	THE MORRIS LAW FIRM, P.C. Response to First Office Action for Application Number 10/167,189, September 29, 2003.					
ML	AS	USPTO, First Office Action for Application Number 10/807,039, September 26, 2005.					
ML	AT	THE MORRIS LAW FIRMS, P.C., Response to First Office Action for Application Number 10/807,039, December 21, 2005.					
ML	AU	HOSOKAWA, et. al., Self-Sputtering Phenomena in High-Rate Coaxial Cylindrical Magnetron Sputtering, J. Vac. Sci. Technol. Vol. 14 No.1, Jan./Feb. 1977, pp 143-146.					
ML	AV	PCT, International Search Report for PCT/US2005/24110 of 31 January 2006.					
ML	AW	PCT, Written Opinion for PCT/US2005/24110 of 31 January 2006.					
ML	AX	PCT, International Preliminary Report on Patentability for PCT/US2005024110 of 26 April 2007.					
EXAMINER			DATE CONSIDERED				
<i>Lavillier</i>			<i>10/13/07</i>				

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

1. The attached cited information should not be construed as an admission that any of the above items are prior art to the subject invention.
2. This is not a representation that a search has been made.

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OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

<i>M</i>	BA	MALIK et. al. Development of an energetic ion assisted mixing and deposition process for TiNx and diamondlike carbon films, using a co-axial geometry in plasma source ion implantation; J. Vac. Sci. Technol., Nov/Dec 1997, 2875-2879, A15, American Vacuum Society.
<i>M</i>	BB	ENSINGER, An Apparatus for sputter coating the inner walls of tubes, Rev. Sci. Instrum, January 1996, 318-321, 67(1), American Institute of Physics.
<i>an</i>	BC	USPTO, First Office Action for Application Number 10/963,341, July, 21, 2006
<i>an</i>	BC	THE MORRIS LAW FIRM, P.C. Response to First Office Action for Application Number 10/963,341, September 15, 2006.
<i>an</i>	BE	USPTO, Second Office Action for Application Number 10/963,341, November 20, 2006.
<i>M</i>	BF	THE MORRIS LAW FIRM, P.C. Response to Second Office Action for Application Number 10/963,341, January 19, 2007.
<i>an</i>	BG	English Translation of Japanese Publication No. JP 4-107268 also referred to as Japanese Patent Application No. H02-224696, Published April 8, 1992, Entitled "Processing Device of Mixed Gas," Inventor: Naoyoshi Fujiwara, Application: TOSHIBA Corporation, pp 381-385.
<i>an</i>	BH	USPTO, First Office Action after RCE for Application Number 10/963,341, February 15, 2007.
<i>M</i>	BI	THE MORRIS LAW FIRM, P.C. Response to First Office Action after RCE for Application Number 10/963,341, April 18, 2007.
<i>M</i>	BJ	USPTO, Second Office Action after RCE for Application Number 10/963,341, July 6, 2007.
<i>an</i>	BK	THE MORRIS LAW FIRM, P.C. Article 19 Amendments for PCT/US2005/24110, March 24, 2006
<i>M</i>	BL	WIPO, WO 2006/044002 A2 International Application for PCT/US Number 2005/024110, April 27, 2006.
<i>M</i>	BM	PCT, International Search Report for PCT/US05/24119, July 11, 2006.
<i>an</i>	BN	PCT, Written Opinion for PCT/US05/24119, July 11, 2006.
<i>M</i>	BO	PCT, International Preliminary Report on Patentability for Application PCT/US05/24119, April 26, 2007
	BP	
	BQ	
	BR	
	BS	
	BT	

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DATE CONSIDERED

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